

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of:

Narwankar, et al.

Application No.: 10/772,893

Filed: February 4, 2004

For: TAILORING NITROGEN PROFILE  
IN SILICON OXYNITRIDE USING  
RAPID THERMAL ANNEALING WITH  
AMMONIA UNDER ULTRA-LOW  
PRESSURE

Examiner: Stouffer, Kelly M.

Art Unit: 1792

Confirmation No.: 5371

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**REPLY UNDER 37 CFR §1.116 EXPEDITED PROCEDURE**

Dear Examiner:

This is in response to the Final Office Action mailed November 24, 2008.

Applicants respectfully request the Examiner to enter this Amendment and consider the following remarks.

**The Listing of Claims** begins on page 2 of this paper.

**Remarks/Arguments** begin on page 11 of this paper.

I hereby certify that this correspondence is being deposited via  
EFS Web on the date below:

January 26, 2009 \_\_\_\_\_  
Date of Deposit

/Gigi Hoover/  
Gigi Hoover \_\_\_\_\_